

TITLE OF INVENTION: REFLECTIVE MASK BLANK AND METHOD FOR
MANUFACTURING THE SAME, AND METHOD FOR INSPECTING REFLECTIVE
MASK BLANK-RELATED SUBSTRATE

ABSTRACT

A reflective mask blank where a reference mark can be detected without erroneously detecting a defect as the reference mark, a method for manufacturing the same and a method for inspecting a reflective mask blank-related substrate. The reflective mask blank includes: a substrate; a multilayer reflective film reflecting exposure light; and an absorber film absorbing the exposure light, the reflective mask blank further including a reference mark serving as a reference position for a defect position and a reference mark forming region for searching for the reference mark, which are formed on a surface on a same side as the multilayer reflective film of the reflective mask blank, the reference mark forming region being formed at a different height from surroundings of the reference mark forming region, the reference mark being formed such that at least a part of the reference mark is included in the reference mark forming region.

[Fig 1]